

AMENDMENTS TO THE SPECIFICATION

Please replace the paragraph beginning at page 1, lines 9-13, with the following rewritten paragraph:

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--This application is a continuation of U.S. Application Serial No. 09/999,636, entitled "Improved Chemisorption for Atomic Layer Deposition," filed October 24, 2001, which is a continuation in part of U.S. Application Serial No. 09/902,080, entitled "Variable Gas Conductance Control For A Process Chamber," filed July 9, 2001. The present application also claims priority from Provisional Application Serial No. 60/281,628, entitled "A Reactor For Atomic Layer Deposition," filed April 5, 2001, incorporated herein by reference.--

Patent Law Group
LLP

2635 North First St.
Suite 223
San Jose, CA 95134
(408) 382-0480
FAX (408) 382-0481